B. Patterning 분과

2017년 2월 15일 (수), 10:10-11:40
Room F (제이드, 2층)

[WF2-B] Patterning and Lithography

좌장: 양현조(SK 하이닉스), 안창남(ASML)

WF2-B-1 **10:10-10:25**	**Influence of Develop Process on the Blob Defect** Ji il Kim, Jinil Kim, Hyungju Jin, Yeongsun Hwang, Dongheok Park, Keundo Ban, Youngsik Kim, and Byoungki Lee *R&D Division, SK hynix Inc.*
WF2-B-2 **10:25-10:40**	**Line-Edge Roughness of Mesoscale Simulation based on Polymer Chain in Extreme Ultra Violet Lithography** Sang-Kon Kim *Department of Science, Hongik University*
WF2-B-3 **10:40-10:55**	**Using Design Based Metrology for Detecting Potential Failure Points of 2D Flash Memory** Min Woo Park, Soo Kyeong Jung, Sun Keun Ji, Hyun Woo Kang, Sang Woo Kim, Jae Kyung Im, Jung Chan Kim, Cheol Kyun Kim, Hyun Jo Yang, and Dong Gyu Yim *R&D Division, SK Hynix Inc.*
WF2-B-4 **10:55-11:10**	**Development of XXnm Defect Inspection System with UV Line Scanning Camera and Anamorphic Illumination** Jin Hwan Kim[1], Han Mo Yang[1], Woo Jun Han[1], Seong Chul Oh[2], Seung Yong Chu[2], and Jai Soon Kim[1] *[1]NEMO Lab, Department of physics, Myongji University, [2]AUROS Technology*
WF2-B-5 **11:10-11:25**	**Optical System Design for the Repair Process of Flat Panel Display** Sang Chul Lee[1], Oh Hyung Kwon[1], Ji Hun Woo[2], Keun Haeng Lee[2], and Jai Soon Kim[1] *[1]NEMO Lab. Department of physic. Myongji University, [2]Charm Engineering Co.Ltd*
WF2-B-6 **11:25-11:40**	**EUV Mask 3D Effect 최소화를 위한 최적 노광 조명계 기술 개발** Inhwan Lee, Yoonsuk Hyun, Sarohan Park, and Changmoon Lim *Research & Development Division, SK Hynix Inc.*